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(71) Applicant *(for all designated States except US)*: **MICRON TECHNOLOGY, INC.** [US/US]; Mail Stop 525, 8000 South Federal Way, Boise, ID 83707-0006 (US).

(72) Inventors; and

(75) Inventors/Applicants *(for US only)*: **PRATT, David, S.** [US/US]; 2282 West Andrew Creek Street, Meridian, ID 83642 (US). **SULFRIDGE, Marc, A.** [US/US]; 4792 South Whitmore Way, Boise, ID 83709 (US).

(74) Agents: **HAMER, Katherine, A.** et al.; Traskbritt, 230 South 500 East, Suite 300, P. O. Box 2550, Salt Lake City, UT 84110-2550 (US).

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(54) Title: METHODS FOR FABRICATING SUB-RESOLUTION ALIGNMENT MARKS ON SEMICONDUCTOR STRUCTURES AND SEMICONDUCTOR STRUCTURES INCLUDING SAME

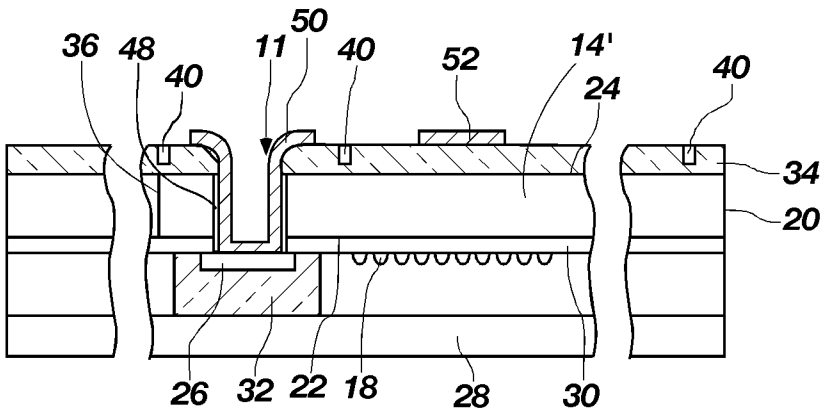


FIG. 1G

(57) Abstract: A method of fabricating semiconductor structures comprising sub-resolution alignment marks is disclosed. The method comprises forming a dielectric material on a substrate and forming at least one sub-resolution alignment mark extending partially into the dielectric material. At least one opening is formed in the dielectric material. Semiconductor structures comprising the sub-resolution alignment marks are also disclosed.

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INTERNATIONAL SEARCH REPORT

International application No.
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A. CLASSIFICATION OF SUBJECT MATTER

H01L 21/60(2006.01)i

According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)
IPC H01L, H03H, B81B, B81C

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched
Korean Utility models and applications for Utility models since 1975
Japanese Utility models and applications for Utility models since 1975

Electronic data base consulted during the international search (name of data base and, where practicable, search terms used)
eKIPASS(KIPO Internal) "alignment" "via"

C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
X A	KR 1020040001454 A(HYNIX SEMICONDUCTOR INC.) 07 January 2004 See abstract; claim 1; Figures 5a-5e	1-6, 12-14, 18, 19 7-11, 15-17, 20
A	US 6146969 A(JUAN BOON TAN et al.) 14 November 2000 See the whole document; column 3; claim 1; Figures 5B & 7B	1-20
A	WO2006/101762 A1(HONEYWELL INTERNATIONAL INC.) 28 September 2006 See the whole document; pages 10 & 12; Figures 8, 9 & 10	1-20

☐ Further documents are listed in the continuation of Box C.

☒ See patent family annex.

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"A" document defining the general state of the art which is not considered to be of particular relevance
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"&" document member of the same patent family

Date of the actual completion of the international search	Date of mailing of the international search report
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Name and mailing address of the ISA/KR	Authorized officer
Korean Intellectual Property Office Government Complex-Daejeon, 139 Seonsa-ro, Seo-gu, Daejeon 302-701, Republic of Korea	CHOI, Jeong Sik
Facsimile No. 82-42-472-7140	Telephone No. 82-42-481-8501

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Information on patent family members

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Patent document cited in search report	Publication date	Patent family member(s)	Publication date
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US 6146969 A	14.11.2000	SG 81276 A1	19.06.2001
WO 2006/101762 A1	28.09.2006	CN 101180794	14.05.2008
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